

10-12-1999

DS

Atty Docket No.: 0902/0085/6SD

FORM PTO-1595
1-31-92



U.S. DEPARTMENT OF COMMERCE
Patent and Trademark Office

101166934

To the Honorable Commissioner of Patents and Trademarks. Please record the attached original documents or copy thereof.

1. Name of conveying party(ies):

PixTech

10-6-99

Additional name(s) of conveying party(ies) attached? Yes No

2. Name and address of receiving party(ies):

Name: Commissariat a l'Energie Atomique

Address: 31-33 rue de la Federation
75752 Paris Cedex 15 France

3. Nature of Conveyance:

- Assignment
- Security Agreement
- Other
- Merger
- Change of Name

Execution Date: October 23, 1997

Additional name(s) and address(es) attached? Yes No

4. Application number(s) or patent number(s):

If this document is being filed together with a new application, the execution date of the application is:

A. Patent Application No.(s)

See attached sheet

B. Patent No.(s)

Additional numbers attached? Yes No

5. Name and address of party to whom correspondence concerning document should be mailed:

OBLON, SPIVAK, McCLELLAND, MAIER &
NEUSTADT, P.C.
Attorneys at Law
Fourth Floor
1755 Jefferson Davis Highway
Arlington, Virginia 22202

6. Total applications and patents involved: **29**

7. Total fee (37 CFR 3.41): \$1,160.00
 Enclosed
 Authorized to be charged to deposit account

8. Deposit account number: 15-0030
(Attach duplicate copy of this page if paying by deposit account)

DO NOT USE THIS SPACE

9. Statement and signature

To the best of my knowledge and belief, the foregoing information is true and correct and any attached copy is a true copy of the original document.

Eckhard H. Kuesters

Name of Person Signing

Signature

10/6/99

Date

Registration Number: 28,870

Total number of pages including this cover sheet: 15

Do not detach this portion

Mail documents to be recorded with required cover sheet information to:

Commissioner of Patents and Trademarks
Box Assignments
Washington, D.C. 20231

10/07/1999 MTHA11 00000321 08256916

01 FC:581

1160.00 0P

PATENT
REEL: 010293 FRAME: 0055

Attachment to PTO 1595

Application Serial Numbers relating to Security Agreement between PixTech and Commissariat
a l'Energie Atomique:

08/256,916 08/614,398

08/256,977 08/615,041

08/290,996 08/618,171

08/676,265 08/660,708

08/371,103 08/660,710

08/322,990 08/837,354

08/491,446 08/850,225

08/363,403 08/841,857

08/390,087 08/883,051

08/390,703 08/278,329

08/413,345 08/352,812

08/403,666

08/504,533

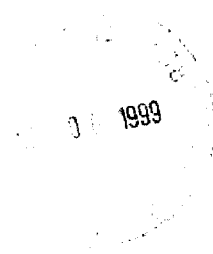
08/619,572

08/511,261

08/633,738

08/534,707

08/602,084



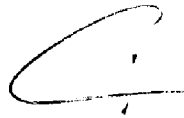
I, Mrs Crespel
c/o ART
BP 114 - 95170 Jumeil-la-Barre - France

declare as follows:

That I am well acquainted with the French and English languages; and

That the attached translation is a true translation into English from the French language.

Made at Paris, this 15 day of September 1999



BETWEEN :

PixTech, *société anonyme*, a limited company organized and existing under French law, with a capital of FF 53 529 600, hereinafter called PIXTECH, having its Registered Office at Avenue Olivier Perroy - Z.I. - 13790 Rousset, represented by Mr. Yves MOREL, Financial and Administrative Manager

AND :

Commissariat à l'Energie Atomique, a scientific, technical and industrial institution (set up under *Ordonnance* N° 2563 dated 18 October 1945 amended), hereinafter called C.E.A. having its Registered Office at 31-33 rue de la Fédération 75752 Paris Cedex 15, represented by Mr. Marc LEGER, Legal and Commercial Relations Manager.

PREAMBLE

Under the terms of a rider n°4, hereinafter called the Rider, dated 23 October 1997 to the licensing agreement they entered into on 17 September 1992, the parties agreed in particular that in consideration of the guarantee (described in article 3 of the Rider) granted by C.E.A. to the Japanese company SUMITOMO relating to possible debts owing by PIXTECH to SUMITOMO, PIXTECH would pledge all the patents and patent applications which it owns and whose ownership it may acquire during the period of validity of the Rider.

The object of this instrument is therefore ;

- to put in pledge the French, foreign and international patents and patent applications which PIXTECH currently holds,
- to organize the terms and conditions for pledging the French, foreign and international patents and patent applications which will be filed or registered by PIXTECH on its own behalf after the signature hereof,
- to organize the release of the pledges that are the subject hereof.

WHEREFORE IT HAS BEEN AGREED AS FOLLOWS :

1/ DESCRIPTION OF THE PATENTS AND PATENT APPLICATIONS PLEDGED ON SIGNING THIS INSTRUMENT

PIXTECH pledges to C.E.A., who accepts, the French, foreign and international patents and patent applications mentioned in the Appendix hereto, hereinafter called the Patents.

PIXTECH declares that the Patents are not under any encumbrance.

The pledging made hereunder will, in respect of the French patents, be registered with the National Patent Registry office, which registration will be made at the expense of PIXTECH by BREVATOME, 25, rue de Ponthieu, 75008 Paris, the agent appointed by the parties.

PIXTECH shall also conduct at its own expense through a local agent chosen by BREVATOME, all registration and other formalities (especially adaptation of the pledging instrument) required by national regulations of each foreign country in which the Patents are filed or registered to assure the validity and enforcement vis-à-vis third parties of this pledging.

2/ PLEDGING OF FRENCH, FOREIGN AND INTERNATIONAL PATENTS AND PATENT APPLICATIONS REGISTERED OR FILED AFTER THE SIGNATURE OF THIS INSTRUMENT.

2-1 Patents not yet registered for which applications have been filed at the date of the present act.

The pledging made hereunder relating to Patent applications not yet registered in France or abroad will be automatically applied, with no further formality being required, to the corresponding patent on its date of issue with retroactive effect starting on the date of registration of the encumbrance on the patent application insofar as the different legal systems concerned allow such retroactive effect.

PIXTECH will keep the C.E.A. informed of developments in registration procedure of patent applications both in France and abroad via a quarterly update of the Appendix which shall be forwarded to the C.E.A. during the first fifteen days of each calendar quarter.

The first update must be sent to the C.E.A. no later than 15 January 1998.

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2-2 Filing of patent applications after the date of signature hereof

In respect of patent applications filed by PIXTECH in France or abroad after the date of signature hereof, the above-mentioned update which PIXTECH is bound to submit to the C.E.A. every quarter will indicate these new filing operations.

These patent applications will all be encumbered in favour of the C.E.A., such pledging to be made each year during the month of the anniversary date hereof, PIXTECH hereby confirming in irrevocable manner the promise of pledging which it gave in article 4 of the Rider.

However, at the express request of the C.E.A, the parties may agree, outside the previously mentioned period, to pledge in favour of the C.E.A. all French, foreign or international patent applications.

In this event, the pledging will come into effect as soon as possible taking into account the required technical period to regularize pledge registration.

2-3 Formalities

PIXTECH shall proceed with the necessary registration formalities required for enforcement of the pledging made hereunder vis-à-vis third parties, in accordance with the modalities specified by paragraph 1.

3/ DECISIONS RELATING TO FILING, EXTENSIONS, WITHDRAWALS OR ISSUE OF PATENTS OR PATENT APPLICATIONS

Should PIXTECH decide not to maintain the validity of one or more French, foreign or international patents and patent applications that are the subject of this pledge agreement, it shall notify the C.E.A. thereof at least two months before the due date so that the C.E.A. may, if it deems fit, continue to maintain validity.

If PIXTECH wishes to withdraw one or more French, foreign and international patent applications that are the subject hereof, it shall notify the C.E.A. beforehand and the parties will consult on the expediency of such withdrawal.

PIXTECH will alone decide on the expediency of filing new French patent applications and their possible extensions to other countries.

4/ RELEASE OF ENCUMBRANCES

At the end of the period of validity of the Rider, the C.E.A. will release all the pledges made hereunder.

Any formalities in connection with this release will be conducted by PIXTECH at its own expense.

5/ POWER OF ATTORNEY

Full powers are hereby given to the bearer of an original copy hereof to carry out or have carried out any formalities - registration, publication, filing and marginal entries - in all places and with any and all administrative authorities whenever required.

Paris this 19th day of May 1998

**Given in nine original copies of which one copy
for the French patent office - I.N.P.I.**

“ Signatures ”

ENTRE :

PixTech, Société anonyme au capital de 53.529.600 F., ci-après dénommée PIXTECH, dont le siège social est Avenue Olivier Perroy - Z.I. -, 13790 Rousset, représentée par Monsieur Yves MOREL, Directeur Financier et Administratif,

d'une part,

ET :

le Commissariat à l'Energie Atomique, Etablissement de caractère scientifique, technique et industriel (institué par l'ordonnance n° 2563 du 18 octobre 1945 modifiée), ci-après dénommé C.E.A., dont le siège est 31-33, rue de la Fédération, 75752 Paris Cédex 15, représenté par Monsieur Marc LEGER, Directeur Juridique et des Relations Commerciales,

d'autre part,

PREAMBULE

Aux termes d'un avenant n° 4, ci-après dénommé l'Avenant, en date du 23 octobre 1997 au contrat de licence qu'elles ont conclu le 17 septembre 1992, les parties sont notamment convenues qu'en contrepartie de la garantie (décrite à l'article 3 de l'Avenant), accordée par le C.E.A. à la société japonaise SUMITOMO concernant les dettes éventuelles de PIXTECH envers SUMITOMO, PIXTECH nantirait l'ensemble des brevets et demandes de brevet dont elle a la propriété ou dont elle acquérera la propriété pendant la période de validité de l'Avenant.

Le présent acte a, dès lors, pour objet :

- de nantir les brevets et demandes de brevet français, étrangers et internationaux dont est, à ce jour, titulaire PIXTECH,
- d'organiser les modalités de nantissement des brevets et demandes de brevet français, étrangers et internationaux qui seront déposés ou enregistrés par PIXTECH et à son profit postérieurement à la signature du présent acte,
- d'organiser la mainlevée des nantissements, objet du présent acte.

CECI EXPOSE, IL EST CONVENU CE QUI SUIT :

1/ DESIGNATION DES BREVETS ET DEMANDES DE BREVET NANTIS DES LA SIGNATURE DU PRESENT ACTE

PIXTECH affecte en nantissement au profit du C.E.A., qui accepte, les brevets et demandes de brevet français, étrangers et internationaux mentionnés en Annexe, ci-après désignés par Brevets.

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PIXTECH déclare que les Brevets ne sont grevés d'aucune inscription de nantissement.

Le présent nantissement fera l'objet, en ce qui concerne les Brevets français, d'une inscription au Registre National des Brevets effectuée, aux frais de PIXTECH, par BREVATOME, 25, rue de Ponthieu, 75008 Paris, mandataire choisi par les parties.

PIXTECH fera également effectuer à ses frais, par l'intermédiaire d'un mandataire local choisi par BREVATOME, toutes les formalités d'enregistrement, d'inscription ou autres (notamment de remise en forme de l'acte) exigées par les réglementations nationales de chaque pays étranger où sont déposés ou enregistrés les Brevets pour la validité et l'opposabilité au tiers du présent nantissement.

2/ NANTISSEMENT DES BREVETS ET DEMANDES DE BREVET FRANCAIS, ETRANGERS ET INTERNATIONAUX ENREGISTRES OU DEPOSES POSTERIEUREMENT A LA SIGNATURE DU PRESENT ACTE

2-1 Brevets non encore enregistrés pour lesquels des demandes ont été déposées à la date du présent acte.

Le présent nantissement portant sur des demandes de Brevets non encore enregistrées en France ou à l'étranger se reportera automatiquement et sans formalité supplémentaire sur le brevet correspondant dès sa délivrance avec effet rétroactif à compter de la date d'inscription du nantissement de la demande de Brevet et ce dans la mesure où les différents systèmes de droit concernés permettent un tel effet rétroactif.

PIXTECH tiendra informé le C.E.A. de l'évolution des procédures d'enregistrement tant en France qu'à l'étranger des demandes de Brevets par une mise à jour trimestrielle de l'Annexe qui sera adressée au C.E.A. dans les quinze premiers jours de chaque trimestre civil.

La première mise à jour devra être adressée au C.E.A. le 15 janvier 1998 au plus tard.

2-2 Dépôt de demandes de brevet postérieur à la signature du présent acte

S'agissant des demandes de brevet déposées par PIXTECH en France ou à l'étranger postérieurement à la signature du présent acte, la mise à jour précitée, qu'est tenue d'adresser PIXTECH au C.E.A. tous les trimestres, mentionnera ces nouveaux dépôts.

Ces demandes de brevet feront toutes l'objet d'un nantissement au profit du C.E.A. effectué chaque année dans le mois de la date anniversaire du présent acte, PIXTECH confirmant par le présent acte de manière irrévocable la promesse de nantissement qu'elle a donné dans l'article 4 de l'Avenant.

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Toutefois, sur demande expresse du C.E.A., les parties pourront convenir, en dehors de la période précitée, du nantissement au profit du C.E.A. de toute demande brevet français, étranger ou international.

Dans ce cas, le nantissement interviendra aussi rapidement que possible compte tenu des délais techniques nécessaires pour régulariser les inscriptions de nantissements.

2-3 Formalités

PIXTECH procédera aux formalités d'inscription et d'enregistrement nécessaires à l'opposabilité aux tiers selon les modalités prévues au paragraphe 1/.

3/ DECISIONS RELATIVES AUX DEPOTS, EXTENSIONS, RETRAITS OU DELIVRANCE DE BREVETS OU DEMANDES DE BREVET

Si PIXTECH décide de ne plus maintenir en vigueur un ou plusieurs des brevets et demandes de brevet français, étrangers et internationaux objet du présent nantissement, elle en avisera le C.E.A. deux mois au moins avant une échéance, afin que le C.E.A. puisse, si bon lui semble, en assurer le maintien en vigueur.

Si PIXTECH désire retirer une ou plusieurs demandes de brevet français, étranger et international objet du présent nantissement, elle en avisera préalablement le C.E.A. et les parties se consulteront sur l'opportunité d'un tel retrait.

PIXTECH décidera seule de l'opportunité du dépôt de nouvelles demandes de brevet français et de leurs éventuelles extensions à l'étranger.

4/ MAINLEVÉE DES NANTISSEMENTS

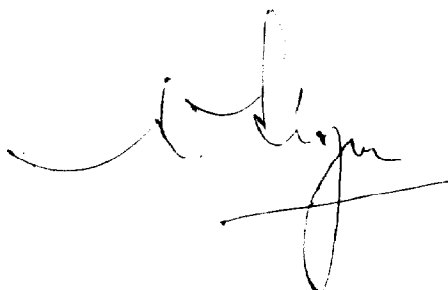
Au terme de la période de validité de l'Avenant, le C.E.A. donnera mainlevée de l'ensemble des nantissements accordés en vertu du présent acte.

Les éventuelles formalités liées à cette mainlevée seront accomplies par PIXTECH à ses frais.

5/ POUVOIR

Tous pouvoirs sont donnés par les présentes au porteur d'un original du présent acte pour requérir ou effectuer toutes formalités - enregistrement, publication, dépôt et mention - partout et dans toute administration où besoin sera.

Paris, le **19 MAI 1998**
Fait en neuf exemplaires dont un
pour l'I.N.P.I.





PixTech's Patents and Applications List

PATREF	N°	Priority Date	Patent description	Inventors	Country	Registration ID	Application	Publication	Examination	Status
	1	PX100 29-Oct-92	Contacts through the substrate: conductive vias cross the glass plate to contact each row and column.	Garcia Michel Grand-Clement Jean-Lu	France	92/13271	29-Oct-92	06-May-94		Active
	2	PX101 04-Dec-92	FED on silicon with one FET under each microlip	Garcia Michel	Europe	94900903.9	03-Dec-93			Under Examination
					France	92/14893	04-Dec-92	17-Mar-95		Active
					Japan	513852/94	03-Aug-94			Exam. Delayed
					USA	08/256,916	03-Aug-94			Application
	3	PX102 04-Dec-92	FED on silicon substrate	Garcia Michel	Canada	2 129 354	03-Dec-93			Under Examination
					France	92/14894	04-Dec-92	08-Jul-94		Active
					Japan	513853/94	03-Dec-93			Exam. Delayed
					USA	08/256,977	03-Aug-94	28-May-96		Active
	4	PX103 29-Dec-92	Spacers stretched during assembly.	Garcia Michel Pépi Richard	France USA	92/16063 08/290,996	29-Dec-92 29-Aug-94	17-Mar-95 20-Aug-96		Active Active
	5	PX105 03-May-93	FED double switched anode. Color stripes (parallel to columns) are split in two groups and biased separately to improve resolution. Combined with PX108	Garcia Michel Meyer Robert	France	93/05541	03-May-93	21-Jul-95		Active
	6	PX106 12-May-93	Assembly under vacuum.	Garcia Michel Pépi Richard (08/676,265)	Europe France Japan USA	PCT 94 01314 93/06008 515776/1996 PCT 94 01314	09-Nov-94 12-May-93 09-Nov-94 09-Nov-94	23-May-96 09-May-95		Active Active Exam. Delayed Application
	7	PX107 16-Jul-93	Fine combs to connect line and columns on the backside	Pépi Richard	France USA	93/09072 08/371,103	16-Jul-93 11-Jan-95	20-Oct-95 26-Nov-96		Active Active

PIXTECH CONFIDENTIAL DATA

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PATREF

N°	Priority Date	Patent description	Inventors	Country	Registration ID	Application	Publication	Examination	Status
8	PX108 14-Oct-93	Double switched anode.	Garcia Michel	Europe France Japan USA	94 41 0089.0 93/12530 273156/94 08/322,990	13-Oct-94 14-Oct-93 13-Oct-94 14-Oct-94	19-Apr-95 19-Jan-98 05-Aug-97		Active Active Exam. Delayed Active
9	PX109 18-Oct-93	Multiple gun evaporation tunnel.	Garcia Michel Meyer Robert Pépi Richard	Europe France Japan USA	94 93 1068.4 93/12709 511402/95 08/491,446	17-Oct-94 18-Oct-93 17-Oct-94 17-Oct-94	27-Apr-95 05-Jan-96 25-Feb-97		Active Active Exam. Delayed Active
10	PX114 03-Dec-93	Process replacing the traditional photolithographic etch. solvent. Local spray on	Garcia Michel	France	93/14829	03-Dec-93			Active
11	PX116 30-Dec-93	Deposition of spacer beads with needle.	Hanon Olivier	France USA	93/16039 08/363,403	30-Dec-93 23-Dec-94	02-Jan-96 30-Jun-96		Active Active
12	PX118 22-Feb-94	Simultaneous etching of gate, dielectric and resistive layer for cathode	Clerc Jean-Frédéric	Europe France Japan USA	95 41 0012.9 94/02291 055178/95 08/390,067	20-Feb-95 22-Feb-94 21-Feb-95 17-Feb-95	25-Jun-97 14-Feb-96		Active Active Exam. Delayed Active
13	PX119 22-Feb-94	Short exhaust tubulation: flat annular shap.	Pépi Richard	France USA	94/02292 08/390,703	22-Feb-94 17-Feb-95	24-May-96 21-May-96		Active Active
14	PX120 31-Mar-94	Suppression of exhaust tubulation using low melting point metal seal.	Clerc Jean-Frédéric	France USA	94/04086 08/413,345	31-Mar-94 30-Mar-95	26-Mar-96 16-Jul-96		Active Active
15	PX121 31-Mar-94	Metal grooves to improve column conductivity.	Bruni Marie-Dominique Garcia Michel	France USA	94/04087 08/403,666	31-Mar-94 14-Mar-95	01-Apr-96		Active Application
16	PX124 21-Jul-94	Cathode metal over the resistive layer.	Bruni Marie-Dominique Clerc Jean-Frédéric	France USA	94/09250 08/504,533	21-Jul-94 20-Jul-95	23-Jul-96		Active Application

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PIXTECH CONFIDENTIAL DATA

PATENT
REEL: 010293 FRAME: 0065

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N°	Priority Date	Patent description	Inventors	Country	Registration ID	Application	Publication	Examination	Status
17	PX123 26-Jul-94	Anode with two metal layers.	Bruni Marie-Dominique (08/619,572)	Europe France Japan USA	95928424.3 94 09491 50553186 95 00 997 PCT	25-Jul-95 26-Jul-94 25-Jul-95 25-Jul-95	30-Jul-95		Active Active Exam. Delayed Application
18	PX126 06-Aug-94	Self-aligned annular resistance around each microtip.	Clerc Jean-Frédéric	Europe France Japan USA	95 410079.8 94/09925 21827395 08/511,261	02-Aug-95 05-Aug-94 04-Aug-95 04-Aug-95	07-Feb-95 06-Aug-96		Active Active Exam. Delayed Application
19	PX128 24-Aug-94	Spacer made of a perforated glass plate.	Clerc Jean-Frédéric (08/633,738)	Europe France Japan USA	95928531.3-22 94/10390 50782896 95 01150 (PCT)	23-Aug-95 24-Aug-94 23-Aug-95 23-Aug-95	26-Sep-96		Under Examination Active Exam. Delayed Application
20	PX130 31-Aug-94	Lateral exhaust queusol.	Hamon Olivier	France	94/10631	31-Aug-94	03-Oct-96		Active
21	PX136 21-Sep-94	Oxide spacer to reduce hole size.	Semena Marie-Noelle	France	94/11471	21-Sep-94			Under Examination
22	PX135 28-Sep-94	Protection of anode by series resistance. Resistive anode.	Couréges Francis Peyre Jean François	China Europe France Japan Korea USA	95 117248.4 95 410112.7PC 94/11806 272072/1995 32108/1995 08/534,707	27-Sep-95 25-Sep-95 28-Sep-94 27-Sep-95 27-Sep-95 27-Sep-95	03-Apr-96 07-Feb-97		Under Examination Under Examination Active Exam. Delayed Under Examination Active
23	PX134 10-Oct-94	Vacuum sealing by glass bead.	Hamon Olivier	France	94/12254	10-Oct-94			Under Examination
24	PX129 30-Nov-94	Sealing with peripheral gasket	Hamon Olivier	France	94/14606	30-Nov-94	26-Sep-96		Active

PIXTECH CONFIDENTIAL DATA

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PATREF	Priority Date	Patent description	Inventors	Country	Registration ID	Appilcation	Publication	Examination	Status
25	PX139 17-Feb-95	Addressing by anode, with current control.	Bancel Bernard	Europe France Japan USA	96410011.9 95102066 052572/1996 08/602,084	08-Feb-96 17-Feb-95 16-Feb-96 15-Feb-96			Active Active Exam. Delayed Application
26	PX143 17-Mar-95	Thick glass FED assembly, without spacers	Sol Jean-Marc	Europe France Japan USA	96 410023.4 95 03376 087132/96 08/614,398	12-Mar-96 17-Mar-95 18-Mar-96 17-Mar-96	18-Sep-96 06-Jun-97		Under Examination Active Exam. Delayed Active
27	PX140 22-Mar-95	Anode with distributed resistance	Courrèges Francis Mougin Stéphane Sol Jean-Marc	Europe France Japan USA	96410029.1 95 03571 091717/96 08/615,041	19-Mar-96 22-Mar-95 22-Mar-96 12-Mar-96	25-Sep-96 13-Jun-97		Under Examination Active Under Examination Active
28	PX142 22-Mar-95	Double gate structure used for multiplexing	Bancel Bernard (08/618,171)	Europe France Japan USA	96 410030.9 95 03570 066366/1996	21-Mar-96 22-Mar-95 22-Mar-96 19-Mar-96	25-Sep-96 16-Jun-97		Under Examination Active Exam. Delayed Application
29	PX146 08-Jun-95	Switched anode with negative voltage	Bancel Bernard	Europe France Japan USA	96410066.3 95 07016 166684/96 08/660,708	04-Jun-96 08-Jun-95 07-Jun-96 06-Jun-96	11-Dec-96 22-Aug-97		Under Examination Active Exam. Delayed Application
30	PX147 08-Jun-95	Anode regeneration. Reset Frame	Bancel Bernard Jäger Axel Thevenet Raymaid (08/660,710)	Europe France Japan USA	96410067.1 95 07017 166683/96	04-Jun-96 08-Jun-95 07-Jun-96 06-Jun-96	11-Dec-96 22-Aug-97		Active Active Exam. Delayed Application
31	PX152 18-Apr-96	Display with hydrogen source	Catalina Philippe Hamon Olivier Mougin Stéphane (08/837,354)	Europe France Japan USA	97410044.8 96/05121 100127/97	15-Apr-97 18-Apr-96 17-Apr-97 17-Apr-97			Under Examination Under Examination Exam. Delayed Under Examination

PIXTECH CONFIDENTIAL DATA

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N°	Priority Date	Patent description	Inventors	Country	Registration ID	Application	Publication	Examination	Status
32	PX149 06-May-96	Use of charge limiting materials for FED anodes.	Mougin Stéphane Oules-Chalon Catherine Reynaud Guy (08/850,225) USA	Europe	97410049.7 96 05930 127816/97	02-May-97 06-May-96 02-May-97 02-May-97			Under Examination Under Examination Exam. Delayed Under Examination
33	PX150 06-May-96	Anode guard rings (08/841,857)	Bancel Bernard Courrèges Francis Mougin Stéphane Rivière-Cazaux Lionel USA	Europe France Japan	97410050.5 96 05931 130553/97	02-May-97 06-May-96 06-May-97 05-May-97			Under Examination Under Examination Exam. Delayed Under Examination
34	PX153 06-May-96	Tetrode device.	Bancel Bernard Grand-Clément Jean-Lu	France	96 05934	06-May-96			Under Examination
35	PX148 31-May-96	Dimming by pulse width modulation	Bancel Bernard Darbols François Peyre Jean François	France	96/06945	31-May-96			Under Examination
36	PX154 02-Jul-96	Microtips regeneration	Bancel Bernard (08/883,051) USA	Europe France Japan USA	97410069.5 96/08487	01-Jul-97 02-Jul-96 02-Jul-97 26-Jun-97			Under Examination Under Examination Exam. Delayed Under Examination
37	PX155 25-Oct-96	Assembly process and apparatus for a flat panel display	Kanagawa Shiroji Mougin Stéphane Sol Jean-Marc Lobel Maurice	France	96/13282_	25-Oct-96			Under Examination
38	PX156 22-Nov-96	Triple grid cathode - Grid addressing	Grand-Clément Jean-Librance Jäger Axel	France	96 14615	22-Nov-96			Under Examination
39	PX157 22-Nov-96	Deviated electrons FED	Jäger Axel	France	96 14616	22-Nov-96			Under Examination

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PATREF	PIXTECH/LETI	Patent description	Inventors	Country	Registration ID	Application	Issue	Examination
1	DD1266 22-jul-93	Grey levels by a mix of time and voltage modulations.	Sarasin Garcia (08/278,329)	Canada Europe France Japan USA	93 09 022	22-jul-93		
2	DD1316 08-déc-93	Dielectric isolation of the anode color stripes	Meyer Montmayeul Boronat Clerc (08/352,812)	Canada Europe France Japan USA	93 14 705	08-déc-93		